

Crystallization Kinetics of Amorphous Alumina-Zirconia-Silica Ceramics

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Nanocrystalline ceramics has a wide potential of applications due to its significantly improved properties such as hardness, strength, abrasion resistance and toughness. Even though nowadays ceramic nanopowder can be conventionally synthesized in large quantities, the consolidation of nanoparticles into mesoscopic structures and large bulk pieces remains a challenge [1]. In the alternative approach such as plasma spraying, the powder compaction step is completely avoided by producing amorphous material by rapid solidification, which can then be thermally treated to introduce nanocrystalline structure by controlled crystallization [2].

Crystallization kinetics of amorphous alumina-zirconia-silica ceramics was studied for seven different material compositions (labeled as NZ, A, B, C, E, F in Fig. 1) based on the bulk cast ceramic material called EucorTM [3]. The amorphous materials were prepared by plasma spraying thus the samples consist of thin splats with a significant chemical variation due to different proportions of Al and Zr oxides in the individual particles of injected powder. Each individual amorphous splat in the as-sprayed materials is, however, chemically homogeneous.

The amorphous materials crystallize above 920°C primarily as tetragonal ZrO₂ solid solution with Al₂O₃ and to a small extent as δ-Al₂O₃ in Al₂O₃-rich splats. The tetragonal zirconia nanocrystallites have average diameters increasing from 10 to 23 nm with increasing silica content (Fig. 2). For silica containing materials the nanocrystallites are embedded in silica rich remains of the amorphous matrix thus creating steep concentration gradients at the nanocrystal/glass interface. The kinetic stabilization of the nanoscale microstructure is related to the silica rejection during growth involving a soft impingement between neighboring nanocrystallites. Based on DSC measurements, the apparent activation energy of the crystallization increases approximately from 900 to 1500 kJ/mol with decreasing silica content. According to the values of Avrami coefficient and on the microstructural observations, crystallization mechanism of the silica containing materials is best described by instantaneous nucleation followed by three dimensional crystal growth controlled by diffusion transport of Zr and Si cations in opposite directions (demixing). The Avrami exponent for the NZ material, however, points to a three dimensional growth mechanism controlled by a reaction at the phase boundary.

References

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- [2] C. Suryanarayana, *J. Miner. Met. Mater. Soc.* (2002) 24.
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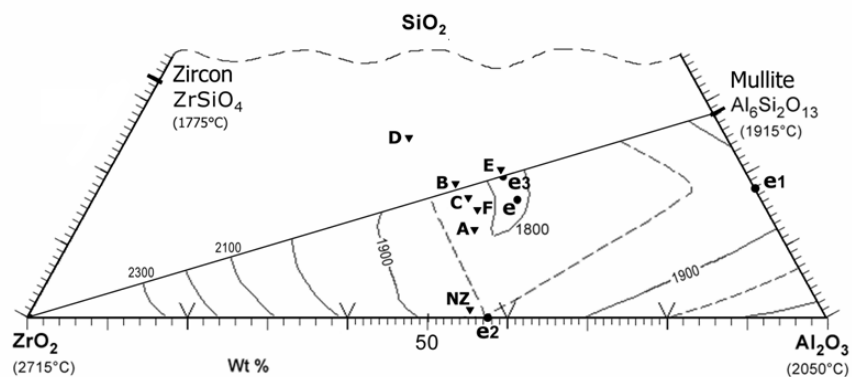


FIG. 1. Part of ternary equilibrium phase diagram showing different compositions of materials used in this study (marked by triangles). e1, e2, e3 – binary eutectic points, e - ternary eutectic point.

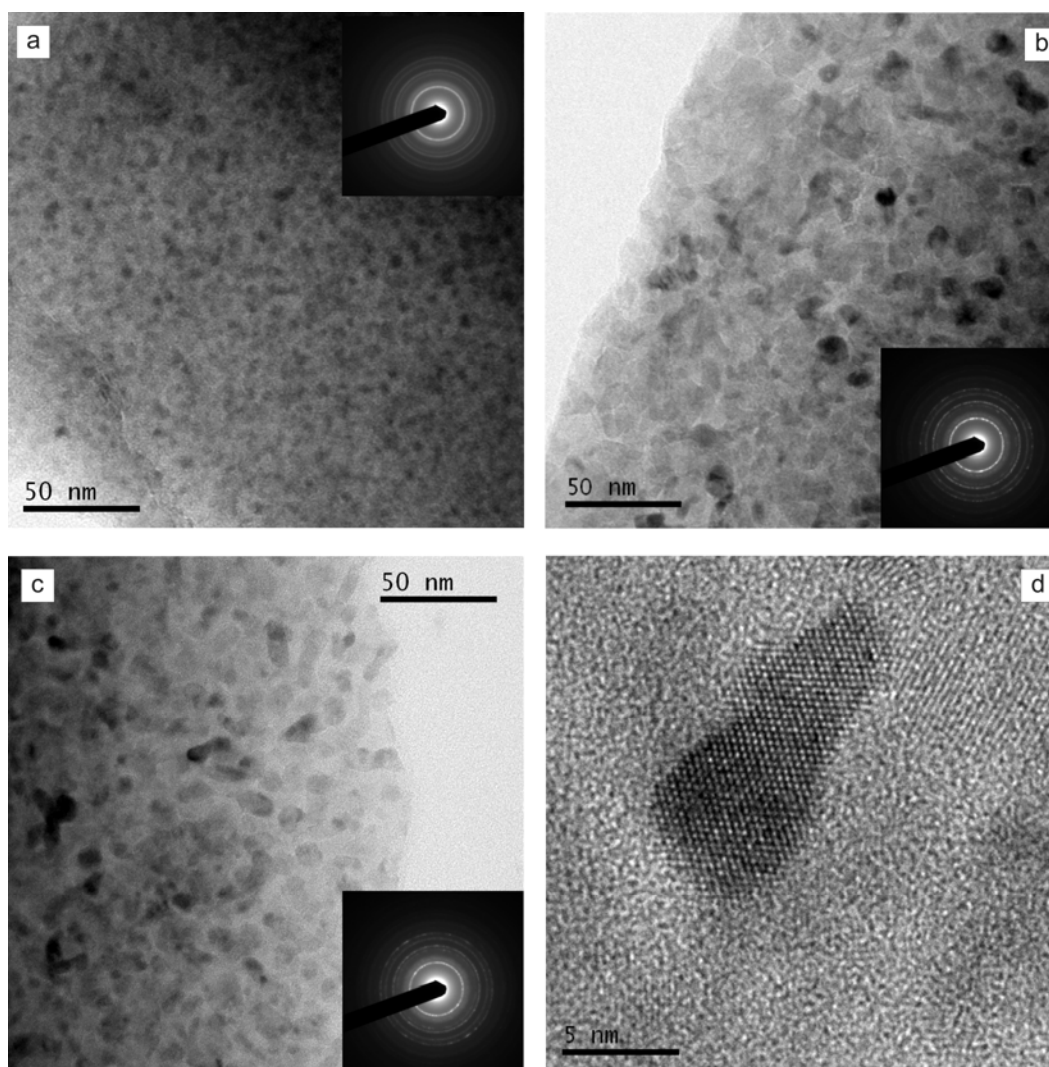


FIG. 2. Bright field TEM and HRTEM micrographs of annealed samples with corresponding diffraction patterns shown as insets. a) NZ, b) A, c) D, and d) a high resolution image of a tetragonal ZrO_2 nanocrystal embedded in a weak contrast amorphous phase.